



Chips Face-up Panelization Approach For Fan-out Packaging

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REV A



Background on FOWLP

Fan-Out Wafer Level Packaging

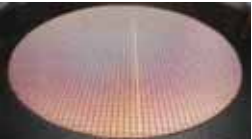
- Chips embedded in molded panel
- IOs fanned in and out over mold surface using polymer and RDL buildup layers

Benefits

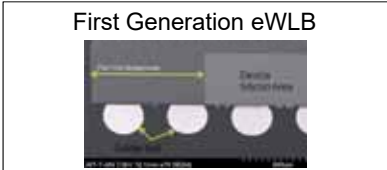
- WLCSP-type packaging for chips with high IO count
- Excellent electrical properties and performance
- Smallest possible package form factor
- No custom substrate required
- Multi-chip and SIP applications

Challenges

Reliability, Yield, Cost



Conventional fan-out

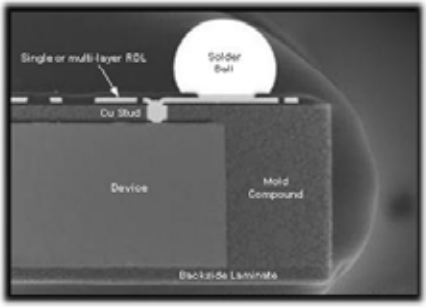
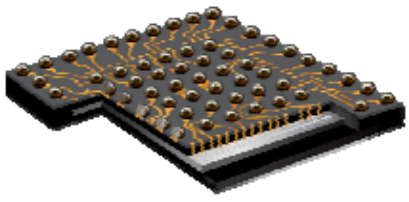




First Generation eWLB

Brunnbauer, M. et. al., "Embedded Wafer Level Ball Grid Array (eWLB)," Electronics Packaging Technology Conference 8th Proceedings, Dec. 2006.

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Chips Face-up FOWLP Deca Technologies

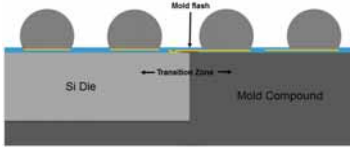
- Front surface of die protected by mold compound
- Cu studs provide current pathways
- Planar surface supports high density RDL
- Adaptive Patterning addresses die shift

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Benefits of Face-up Approach Deca Technologies

Challenges with exposed die in conventional structure

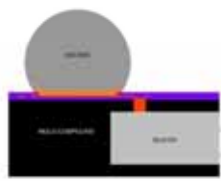
- Mold flash
- Protruding metal from chip singulation
- Polymer or RDL cracking at silicon-mold transition
- Silicon die has poor CTE match to PCB



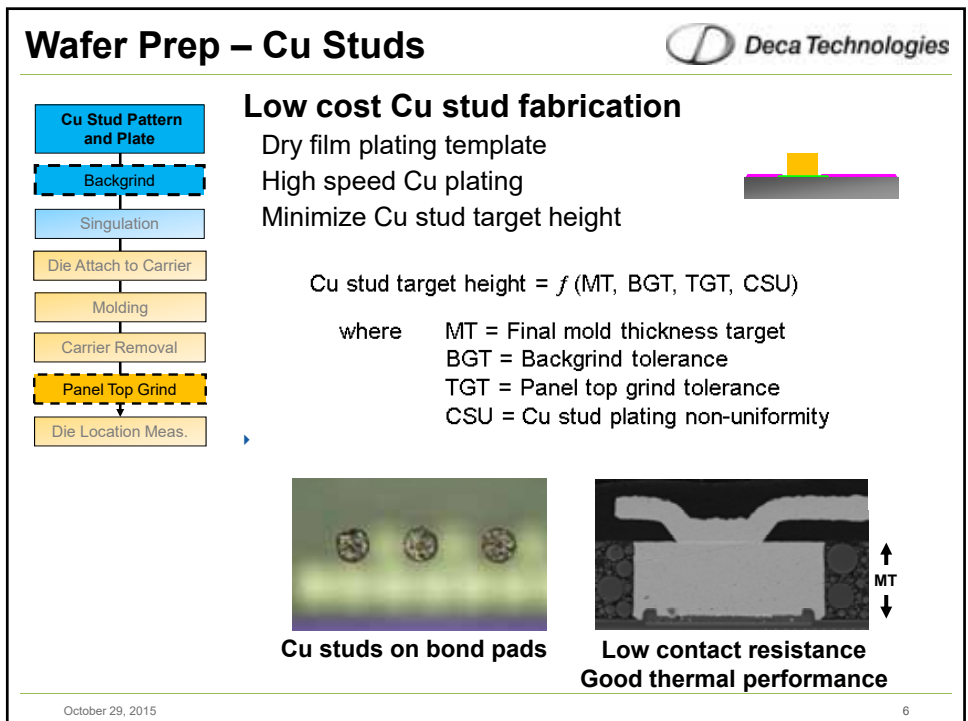
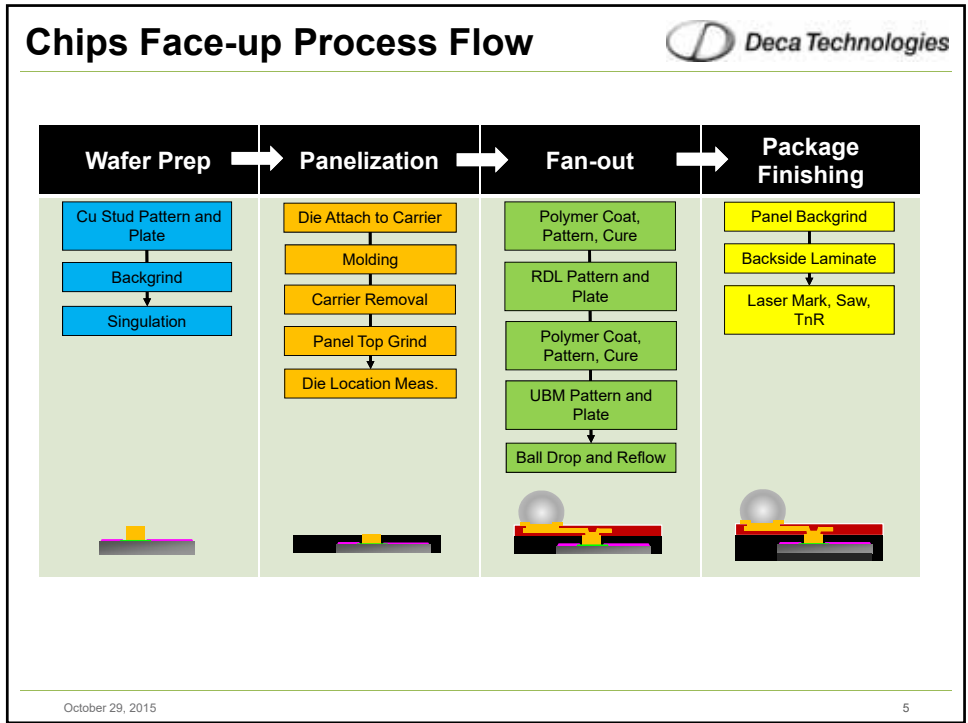
Conventional fan-out structure

Chips Face-up FOWLP

- Rugged package with encased die
- No discontinuity at die edge
- Improved BLR performance



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Wafer Prep – Backgrind and Singulation

Backgrind
Optimize silicon thickness for panel warpage control

Singulation
Standard laser groove and wafer saw



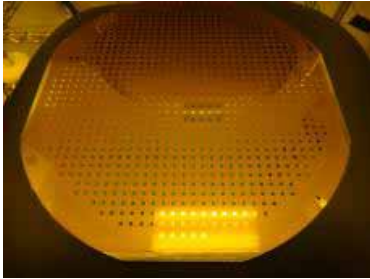
Process Flow:

- Cu Stud Pattern and Plate
- Backgrind**
- Singulation**
- Die Attach to Carrier
- Molding
- Carrier Removal
- Panel Top Grind
- Die Location Meas.

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Panelization – Die Attach

Die Attach
Chips placed face-up on release tape & carrier
Placement accuracy can affect overlay, yield
Serial process -> significant costs

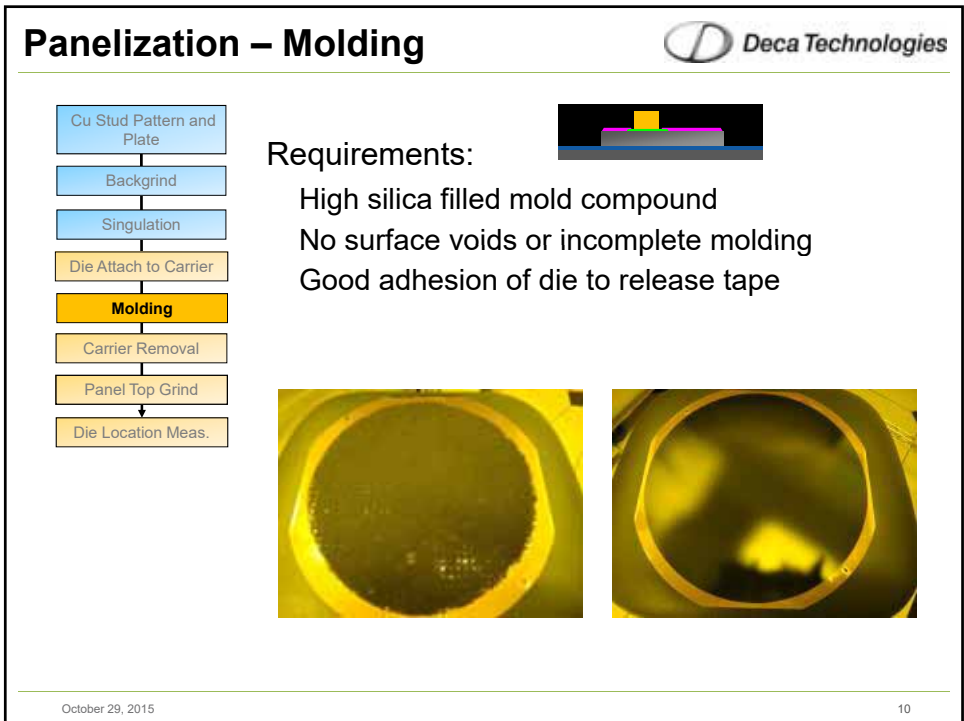
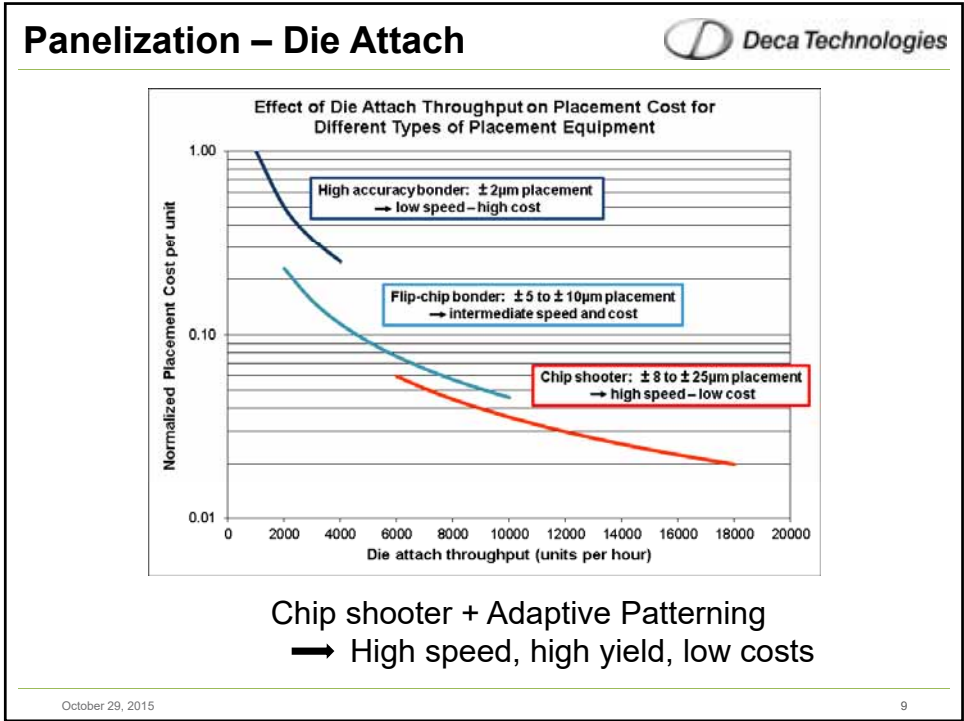


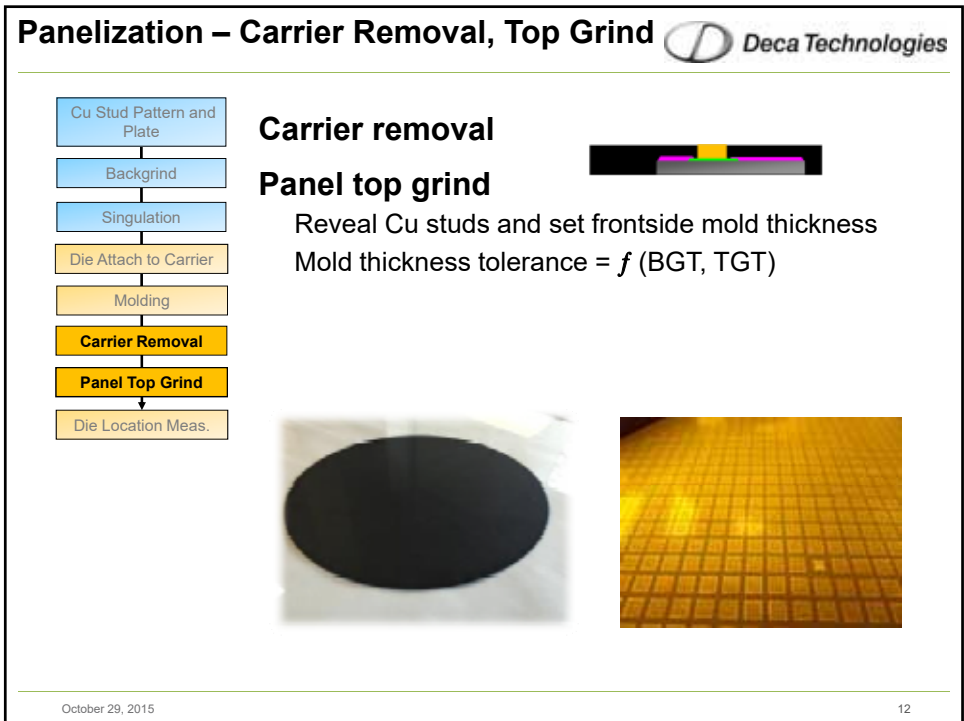
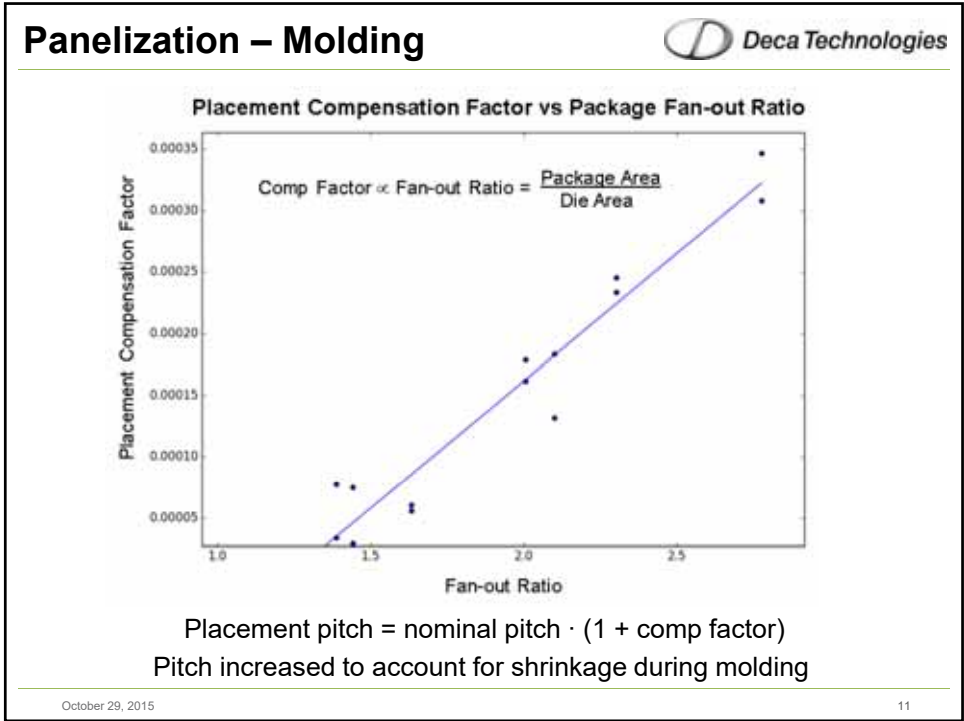
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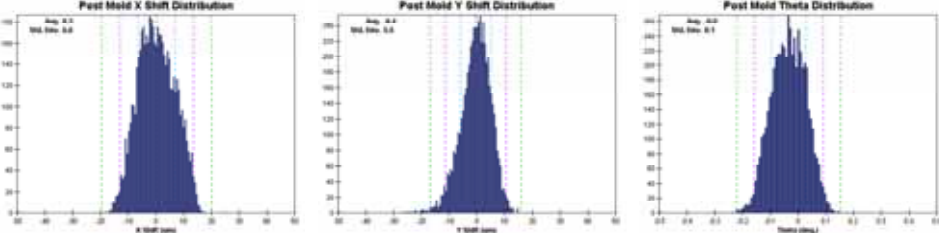
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Panelization – Die Location Measurement

Optical scanner used to determine position and rotation of every die on the panel



Measured X, Y, and angle shifts
3mm X 3mm package on a 300mm panel
Control $\sim \pm 20\mu\text{m}$ in X and Y, ± 0.2 degrees in theta

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Adaptive Patterning


Customization of design on each package to match actual die location

Process Flow

- Inspect Cu stud pattern to determine true position and rotation of each die
- Import and optimize die position data in Adaptive Patterning software
- Generate adaptive via and RDL patterns for each unit on the panel
- Export physical layout of the whole panel for each layer
- Expose on lithography system which dynamically implements the unique design per panel

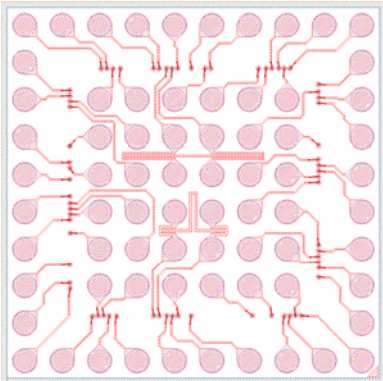
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Adaptive Patterning Methods



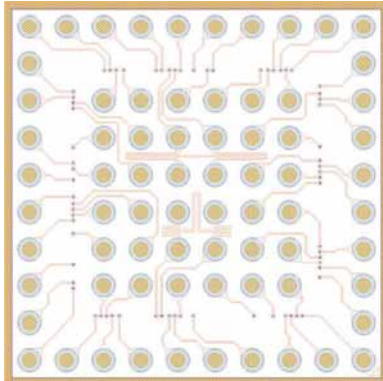
Adaptive Routing

Dynamically adapts RDL routing to accurately align to true die position




Adaptive Alignment

Aligns the entire RDL layer to true die position within the unit



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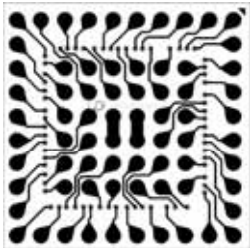
Adaptive Routing



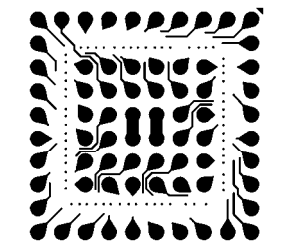
Dynamically adapts Via1 and a portion of RDL pattern of each individual package to align to the true position of each die

Via2, UBM and BGA pattern fixed with respect to package edge

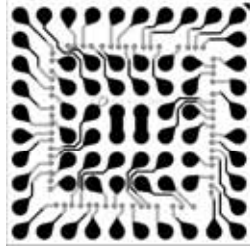
1) Create a nominal fan-out RDL design



2) Omit a small portion of the RDL design near the die pads (prestratum)

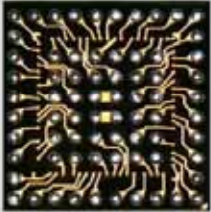
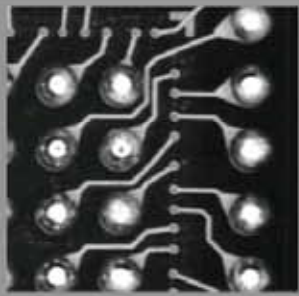



3) Complete the design after measuring the true position of each chip



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Effectiveness of Adaptive Routing Deca Technologies

 <p>Deca 4 × 4mm² Package</p>		
<p>Offsets from design position:</p>	<p>X = -4.4µm Y = +5.7µm Angle = -0.01°</p>	<p>X = +8.2µm Y = -21.0µm Angle = +0.13°</p>

Minimal adjustment in RDL trace lengths, typically 10 to 20µm

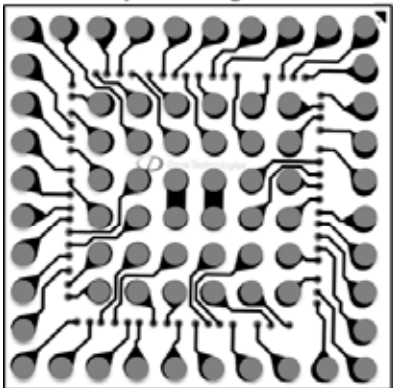
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Adaptive Alignment Deca Technologies

Entire RDL layer and Via1 shift to match die shift; misalignment is effectively moved to the UBM stack

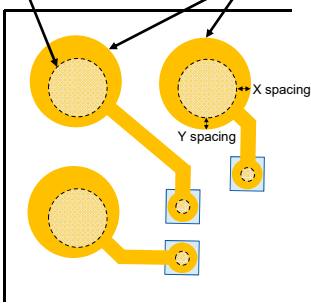
Via2, UBM and BGA patterns remain fixed with respect to package edge

Adaptive Alignment

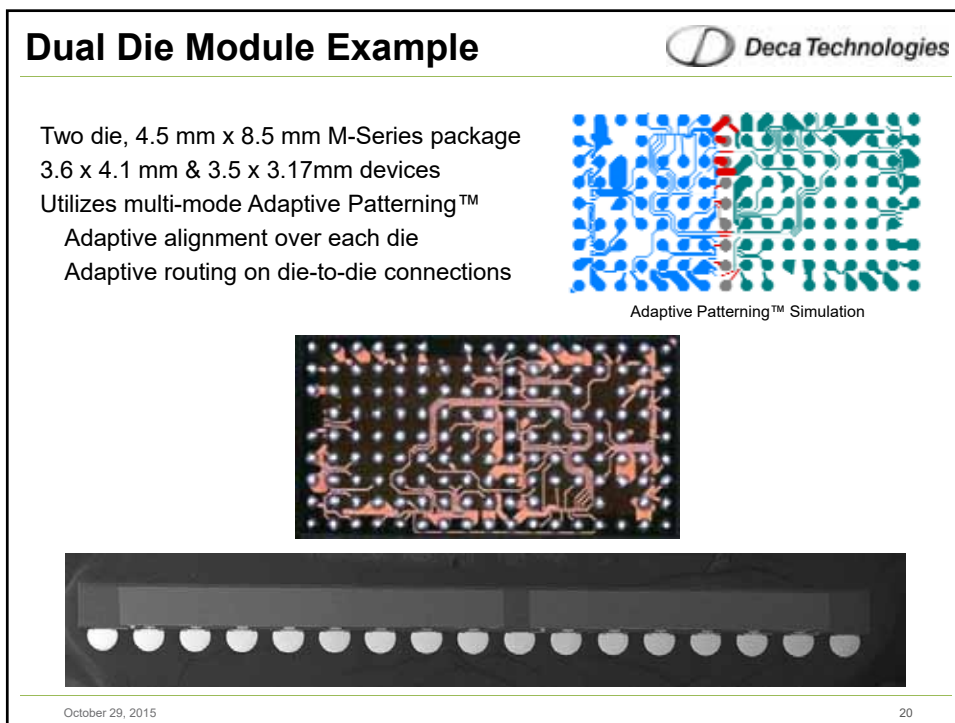
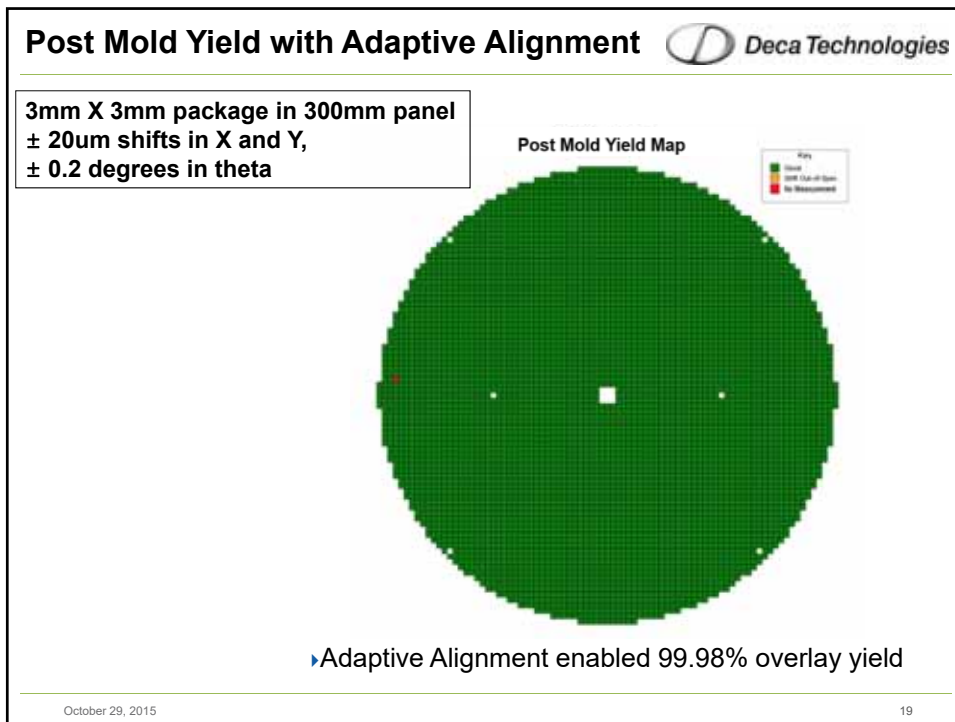


Via2 slightly undersized; via2 and bump locations held constant


Via1 and RDL patterns adapted for die shift

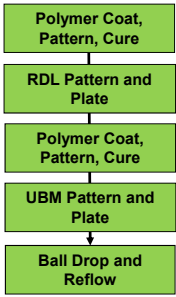


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Fan-out



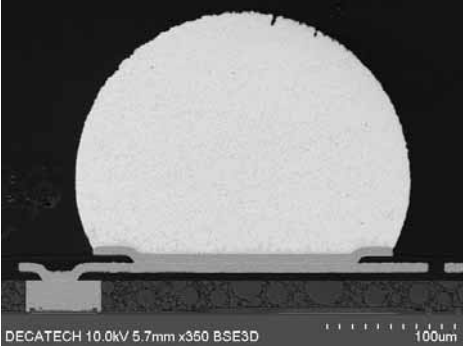


Conventional build-up: polymer 1, RDL, polymer 2, UBM layers + ball drop and reflow

Unique Adaptive Patterning design files facilitate good overlay to chips and Cu studs


Planar mold surface supports high density RDL wiring

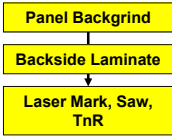
Mold layer provides good inductor performance



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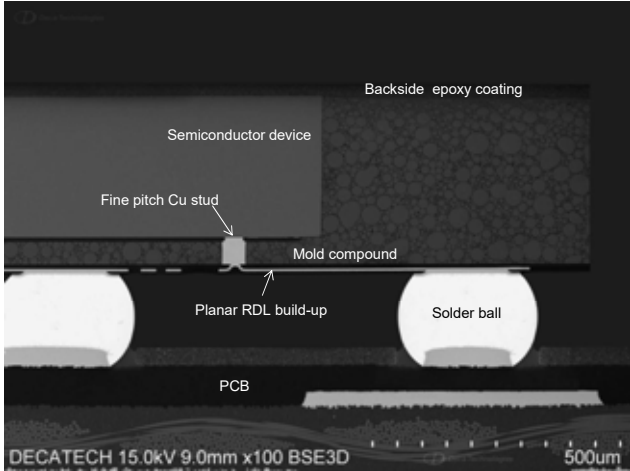
Package Finishing





Package finishing used to complete part


Optional backside laminate for fully encased structure



Fully assembled M-Series part

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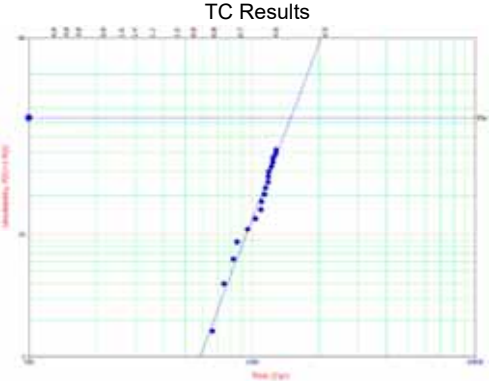
BLR on 8x8mm Full Array TV




Passed BLR requirements at 8mm X 8mm body size

Test Vehicle	Testing Status	Drop Results	Cycling Results
Full Array 8X8 mm ²	Completed 1500 cycles and 1000 drops	No failures to 256 drops	First failure at 665 cycles

TC Results






Deca internal TV:
8x8mm full array

Testing of larger body sizes currently underway

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FOWLP Cost Challenge



Conventional approach utilizes wafer fab equipment for build up layers
New approach: Use of solar-based processes

Solar processes applicable to FOWLP


- Patterned polymer
- Sputtered barriers and seed layers
- Electroplated metals
- Thin, warped wafer handling



6" solar wafers

Solar-like wafer and panel flow line created for FOWLP processing

- Low capital investment
- High throughput: > 100 wafers or panels per hour for wafer prep and fan-out processes




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FOWLP Manufacturing Formats

Currently 300mm round, with large panel in development

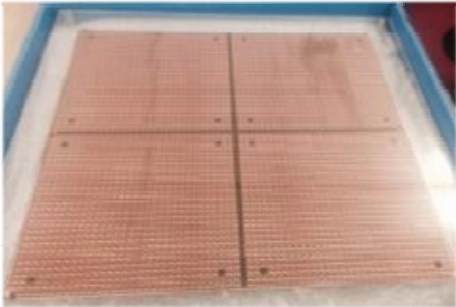
Initial production



300mm round

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Large Panel Future Production



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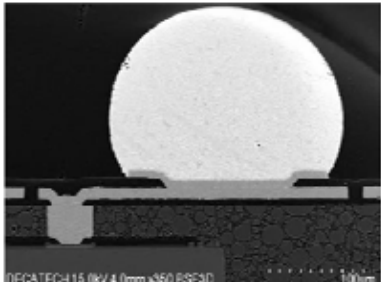
Summary

Advantages of chips face-up approach with Adaptive Patterning:

- 1) Low contact resistance to Al pads
- 2) Low chip attach costs
- 3) High yields through mold and Via1 overlay
- 4) Tight ground rules
- 5) Fully protected die edge
- 6) Planar surface for fine pitch RDL
- 7) Good RF performance
- 8) Robust BLR

Challenges:

- Minimizing wafer prep costs
- Control of grind tolerances



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Thank You